Supplementary materials

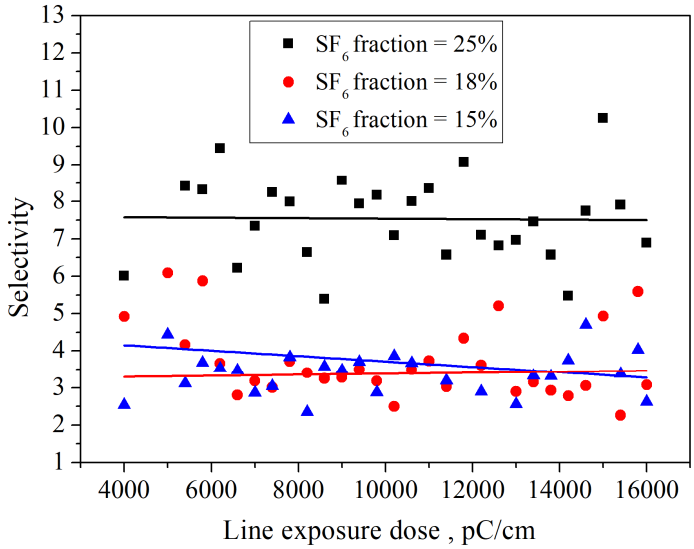


Figure S1. Dependence of selectivity on exposure dose for etching processes with different values of SF_6 fraction.